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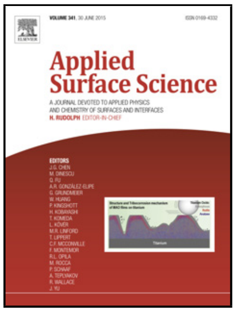

Title: Wafer-scale, conformal and direct growth of MoS_2 thin filmsby atomic layer deposition

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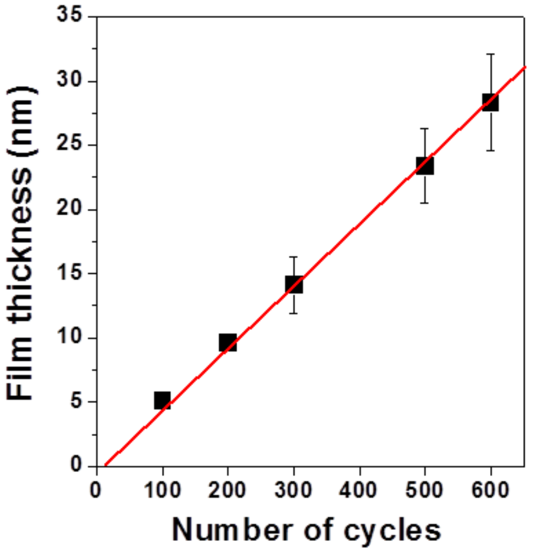
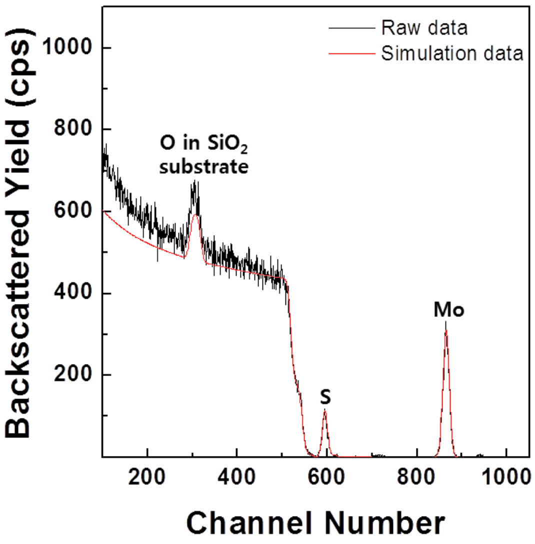
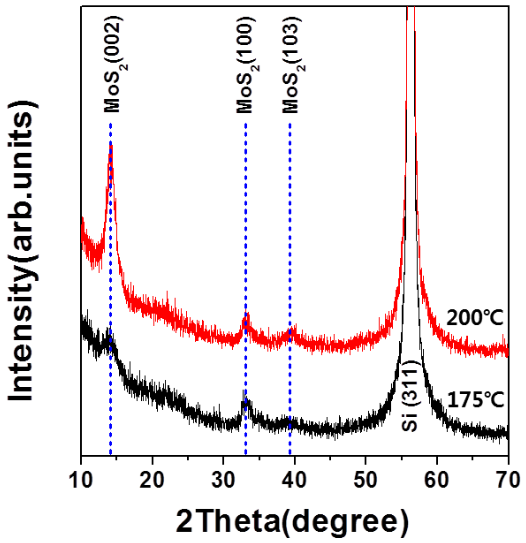
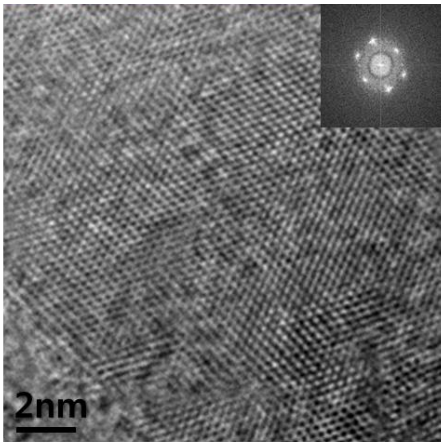
ALD of MoS_2 thin films and nanosheets using $Mo(CO)_6$ and H_2S plasma









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